

Abstract

The invention relates to a device and a method for producing resist profiled elements. According to the invention, an electron beam lithography system is used to produce an
5 electron beam, the axis of the beam being essentially perpendicular to a resist layer in which the resist profiled element is to be produced. The electron beam can be adjusted in terms of the electron surface dose in such a way that a non-orthogonal resist profiled element can be produced as a result of the irradiation by the electron beam.